

# PATENT ABSTRACTS OF JAPAN

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## (54) SILVER HALIDE COLOR PHOTOGRAPHIC SENSITIVE MATERIAL HAVING EXCELLENT RAPID PROCESSING ADAPTABILITY AND PRESERVABLE PROPERTY

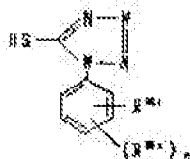
(57)Abstract:

PURPOSE: To suppress the increase of fogging in rapid processing and to improve the preservable property with age by incorporating a specific mercapto compd. into silver halide emulsion adhesive layers and incorporating a compd. which can scavenge oxides by reacting with the oxidation product of a developing agent into hydrophilic protective colloidal layer.

CONSTITUTION: This photosensitive material is formed by applying the hydrophilic protective colloidal layers contg. the photosensitive silver halide emulsion adhesive layers on a substrate. The mercapto compd. expressed by the formula I is incorporated into the silver halide emulsion adhesive layers and the compd. which can scavenge the oxides reacting with the oxidation product of the developing agent is incorporated into the hydrophilic protective colloidal layers. In the formula, Rm1 denotes -NHCORm3, -NHSO2Rm4; Rm1, Rm4 denote an alkyl group, aryl group; Rm2 denotes a halogen atom, nitro group, cyano group, amino group, sulfo group, etc.; n denotes 0 to 4. The increase of the fogging by the rapid color development processing is decreased in this way and the preservable stability under high-temp. and high-

humidity conditions is improved without degrading the sensitivity.

(11)



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### LEGAL STATUS

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